

Docket No.: MIY-0211
(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Masanori NAKAMURA et al.

Application No.: New Application

Confirmation No.: Not Yet Assigned

Filed: Concurrently Herewith

Art Unit: N/A

For: POSITIVE PHOTORESIST AND METHOD
FOR PRODUCING STRUCTURE

Examiner: Not Yet Assigned

FIRST PRELIMINARY AMENDMENT

MS Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

INTRODUCTORY COMMENTS

Prior to examination on the merits, please amend the above-identified U.S. patent application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 9 of this paper.